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(54) **SPUTTER TARGET FOR A PHYSICAL VAPOR DEPOSITION CHAMBER**

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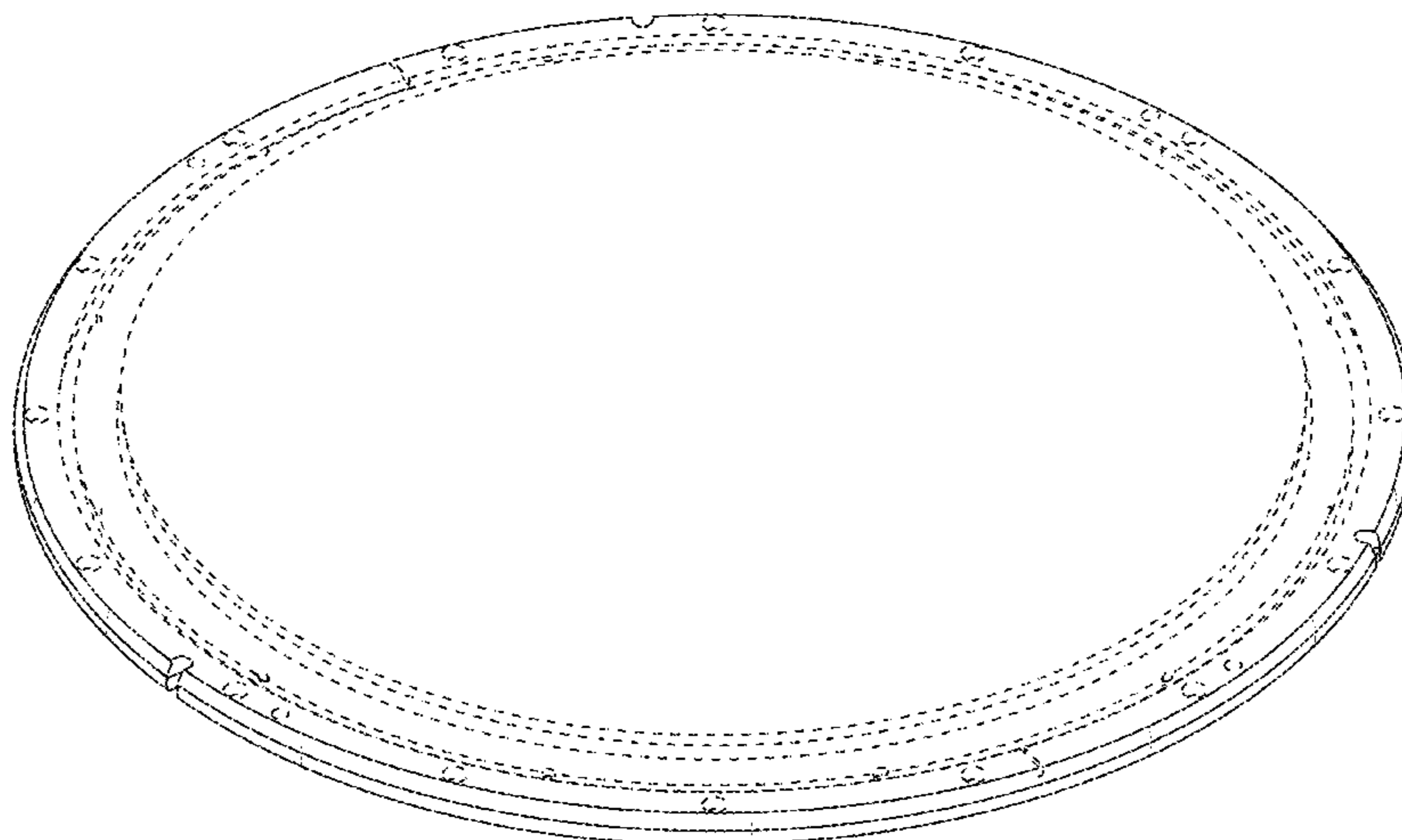
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Related U.S. Application Data

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See application file for complete search history.



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(57) CLAIM

We claim the ornamental design for a sputter target for a physical vapor deposition chamber, as shown and described.

DESCRIPTION

FIG. 1 is a top isometric view of a sputter target for a physical vapor deposition chamber, according to our novel design.
FIG. 2 is a top plan view thereof.
FIG. 3 is a bottom plan view thereof.
FIG. 4 is a right elevation view thereof.
FIG. 5 is a left elevation view thereof.
FIG. 6 is a front elevation view thereof.
FIG. 7 is a back elevation view thereof; and,
FIG. 8 is an enlarged cross-sectional view taken along line 8-8 in FIG. 2.
The dashed lines in FIGS. 1-8 represent unclaimed environment and form no part of the claimed design.

1 Claim, 5 Drawing Sheets

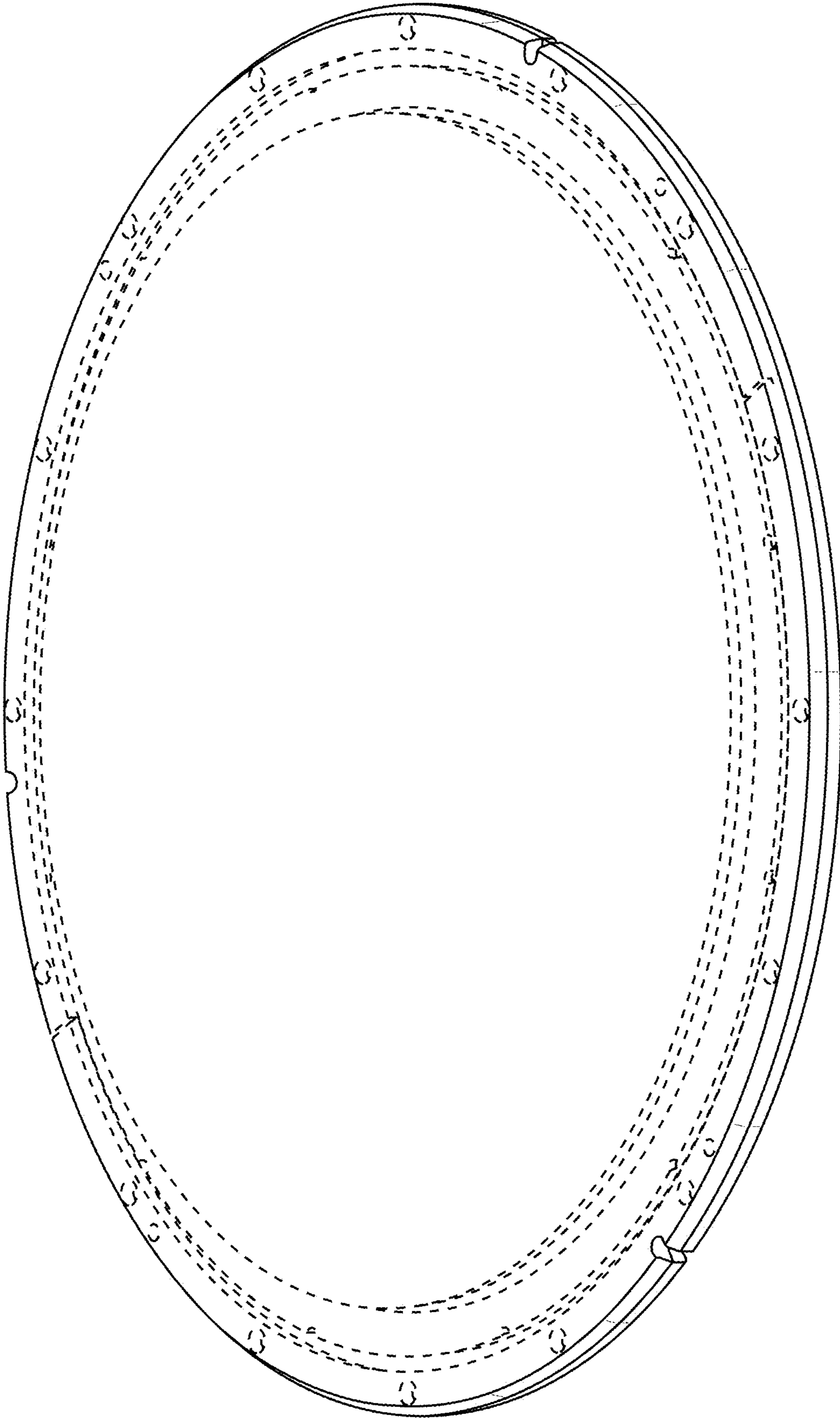


FIG. 1

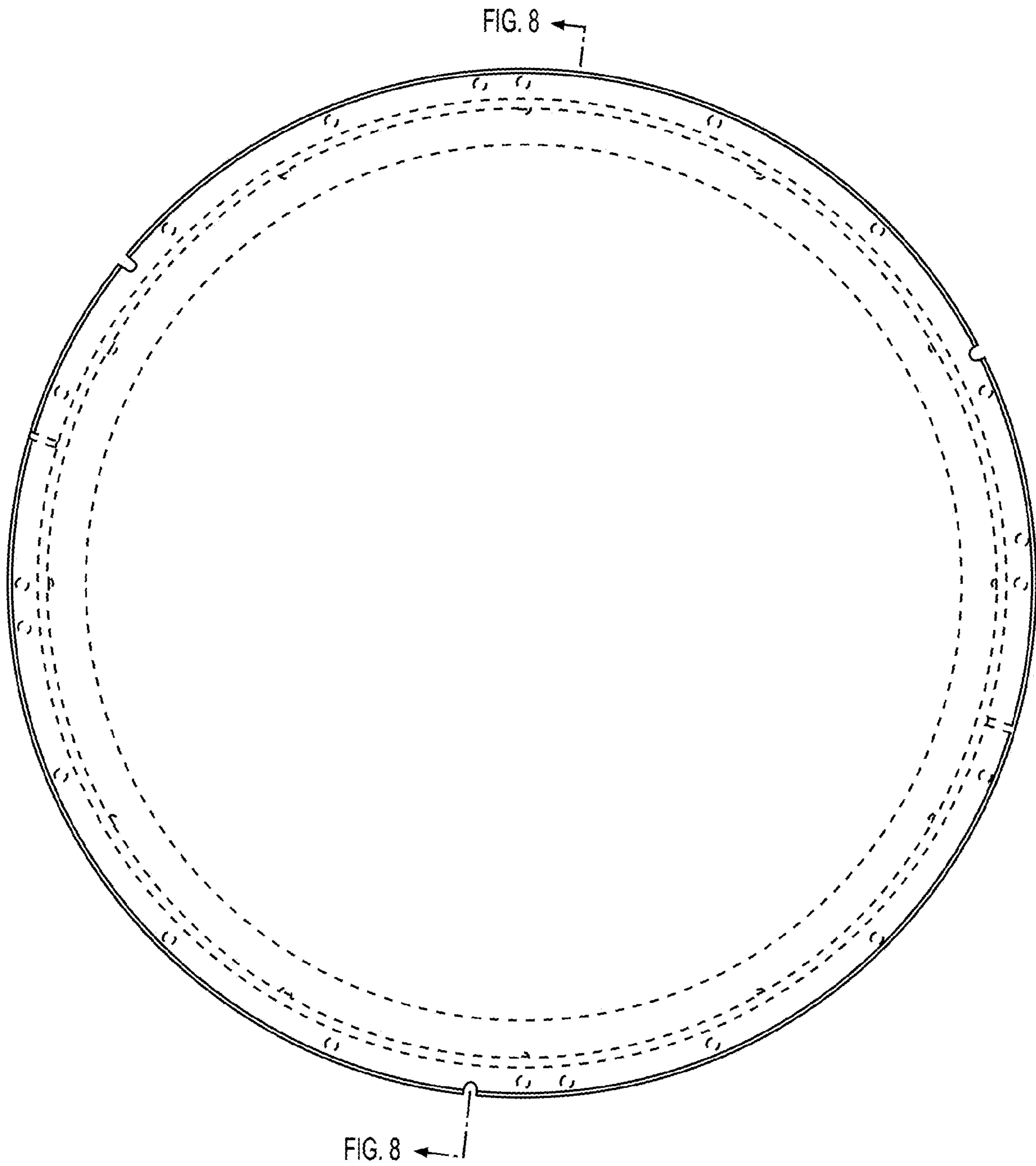


FIG. 2

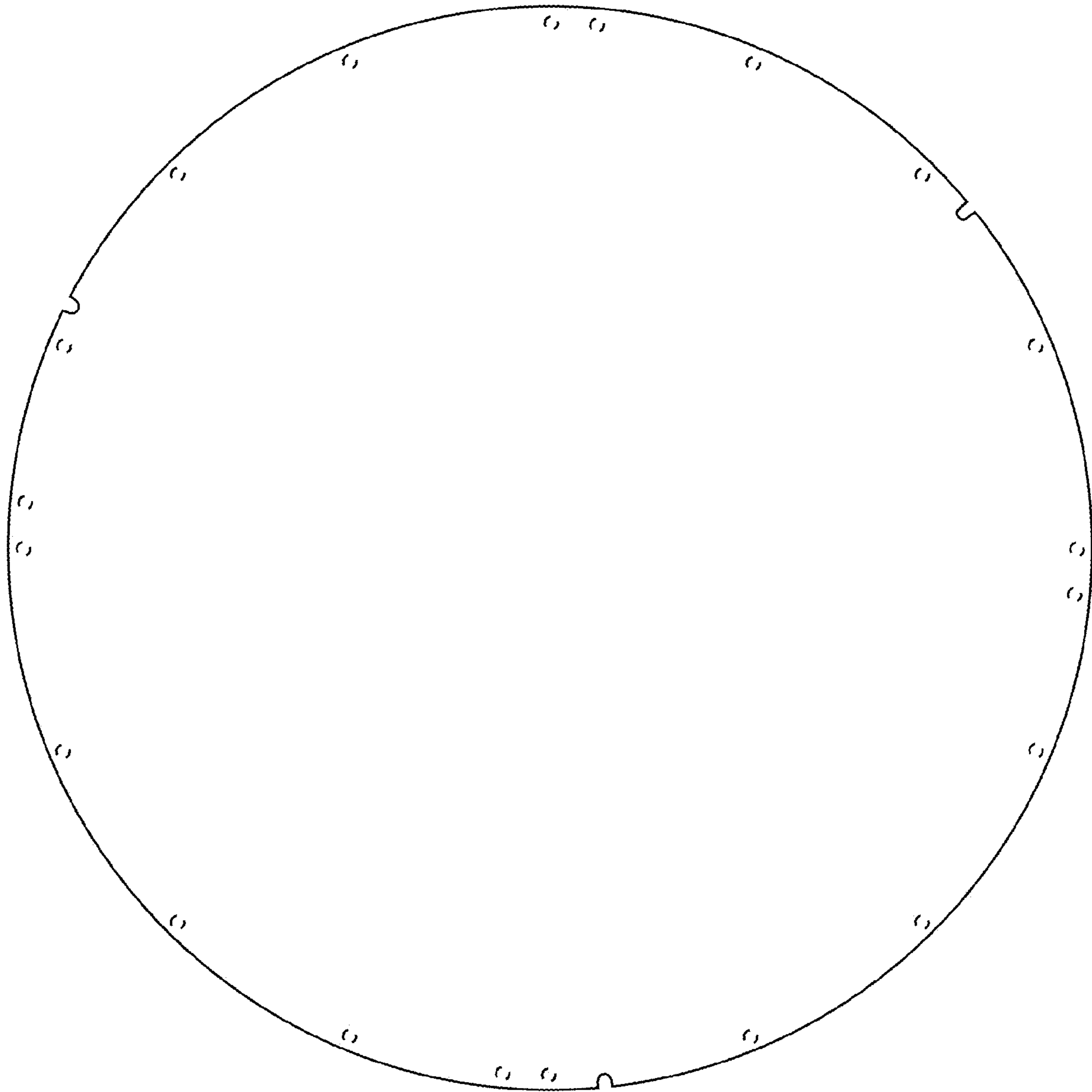


FIG. 3

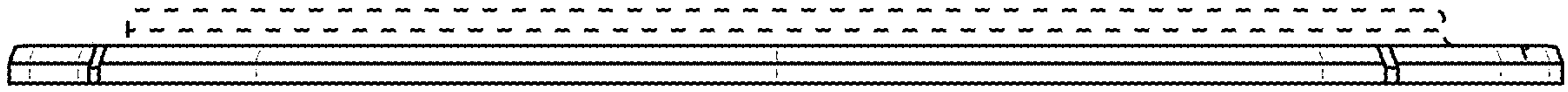


FIG. 4

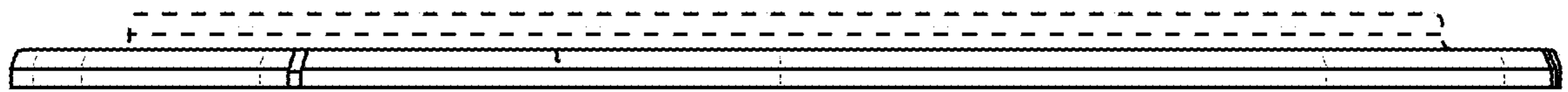


FIG. 5

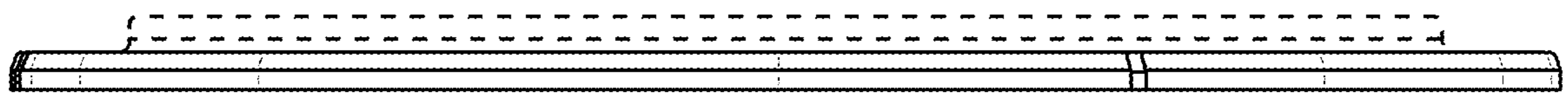


FIG. 6

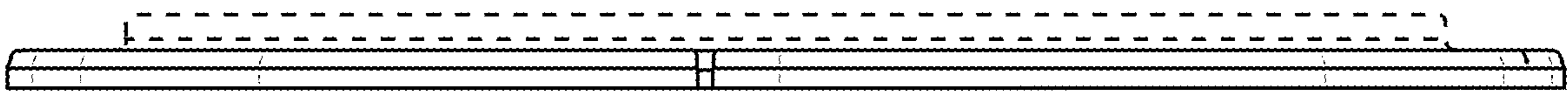


FIG. 7

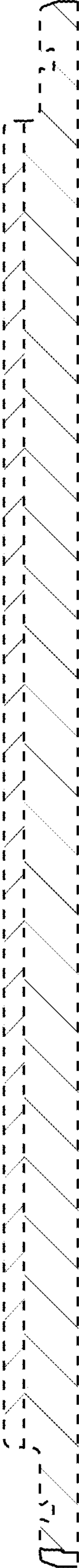


FIG. 8